

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
27 September 2007 (27.09.2007)

PCT

(10) International Publication Number
WO 2007/109491 A3

- (51) International Patent Classification:
H01L 21/84 (2006.01) H01L 21/8238 (2006.01)
- (21) International Application Number:
PCT/US2007/064038
- (22) International Filing Date: 15 March 2007 (15.03.2007)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
11/378,101 17 March 2006 (17.03.2006) US
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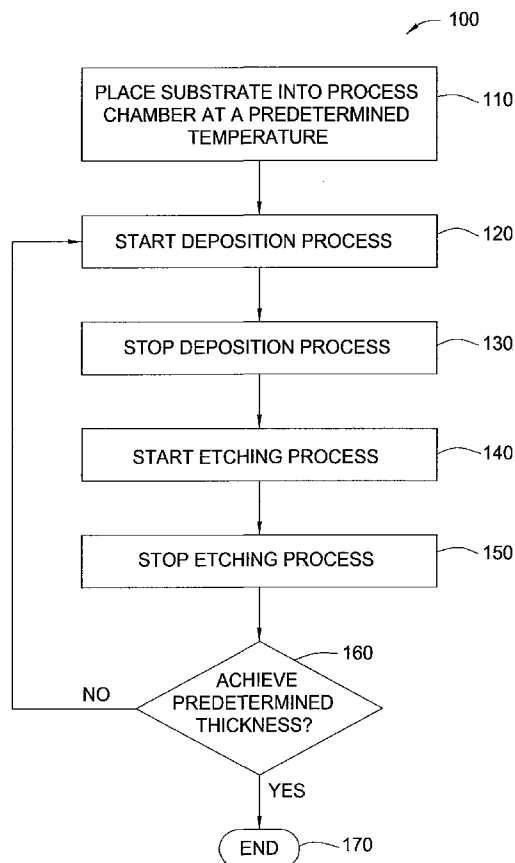
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(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI,

[Continued on next page]

(54) Title: SELECTIVE DEPOSITION



(57) Abstract: A method for epitaxially forming a silicon-containing material on a substrate surface utilizes a halogen containing gas as both an etching gas as well as a carrier gas through adjustments of the process chamber temperature and pressure. It is beneficial to utilize HCl as the halogen containing gas because converting HCl from a carrier gas to an etching gas can easily be performed by adjusting the chamber pressure.

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FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

Published:

- *with international search report*
- *before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments*

(88) Date of publication of the international search report:

13 December 2007

INTERNATIONAL SEARCH REPORT

International application No.
PCT/US 07/64038

A. CLASSIFICATION OF SUBJECT MATTER
IPC(8) - H01L 21/84; H01L 21/8238 (2007.01)
USPC - 438/149; 257/E21.102
According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
see keywords below.

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched
pubWEST (DB=PGPB,USPT,USOC,EPAB,JPAB; PLUR=NO; OP=ADJ)

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)
PubWEST (DB=PGPB,USPT,USOC,EPAB,JPAB; PLUR=NO; OP=ADJ); freepatentsonline.com; WIPO; Google Scholar; keywords:
polycrystalline, monocrystalline, process chamber, second flow rate, second surface, additional surface, epitaxial, substrate, amorphous,
deposition gas, chamber pressure, methyl chloride, dichloromethane, chloroform

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
Y	US 2005/0079691 A1 (KIM et al.) 14 April 2005 (14.04.2005), entire document, especially para [0006]-[0013], [0023], [0044], [0018], [0021], [0009], [0010], [025], [0029], [0031], 0032], [0045],	1-36
Y	US 2006/0046442 A1 (RAMASWAMY) 02 March 2006 (02.03.2006), entire document, especially para [0039]	1-36
Y	US 2003/0022528 A1 (TODD) 30 January 2003 (30.01.2003) see entire document, especially para [0047]	9, 10, 21 and 22
A	US 2004/0259333 A1 (TOMASINI et al.) 23 December 2004 (23.12.2004), entire document	1-36


Further documents are listed in the continuation of Box C.

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Date of the actual completion of the international search
19 September 2007 (19.09.2007)

Date of mailing of the international search report
17 OCT 2007

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